**SOLITEC VACUUM HOTPLATE**

**LOCATION:** Optical Lithography

**PRIMARY TRAINER:** Stephanie Bozic (2-6724, sbozic@ualberta.ca)

**SECONDARY TRAINER:** Jolene Chorzempa (2-4823, jolenec@ualberta.ca)

1. **OVERVIEW**

   The hotplate is used to soft or hard bake photo resists after they have been spun onto substrates. The Solitec Vacuum hotplate is used for silicon substrates and silicon substrates with thin films.

2. **SAFETY PRECAUTIONS**

   Photo resist is a solvent based chemical which has been known to cause problems in reproduction, especially in males. It is considered hazardous waste and should be collected in solvent waste either as a liquid or a solid. The hot plate is vented to reduce vapors.

   If you are bringing any new materials into the NanoFab for use in your process, it is necessary to fill out a chemical import form (available on our website, http://www.nanofab.ualberta.ca) and supply an MSDS data sheet to Stephanie Bozic.
3. OPERATING INSTRUCTIONS

3.1 Turn the power button on and ensure the hotplate is set to the appropriate temperature.
3.2 Adjust the temperature using the temperature adjust buttons. The set temperature is displayed in green and the actual temperature is displayed in red.
3.3 This hotplate takes about 5-10min to reach a set temperature of 115°C
3.4 The wafer can be placed on the hotplate when the set temperature is reached.
3.5 Set the Bake time.
3.6 Press Start/Stop to begin the bake.

4. TROUBLESHOOTING

If you encounter an unexpected error or require assistance please contact the primary or secondary trainer listed above. Should they not be available, please contact any staff member for assistance.

6. APPROVAL

QUALIFIED TRAINER:  Jolene Chorzempa
TRAINING COORDINATOR:  Stephanie Bozic